

Supporting information

Direct Nanopatterning of Polymer/Silver Nanocubes Using Low Energy Electron Beam Irradiations

Abdel-Aziz El Mel,[†] Nicolas Stephant and Romain Gautier

Institut des Matériaux Jean Rouxel, Université de Nantes, CNRS, 2 Rue de la Houssinière B.P. 32229, 44322 Nantes cedex 3, France.

[†]Corresponding author: Abdelaziz.elmel@cnrs-immn.fr, Telephone: +33 (0) 240 376325, Fax: +33 (0) 240 373 959.

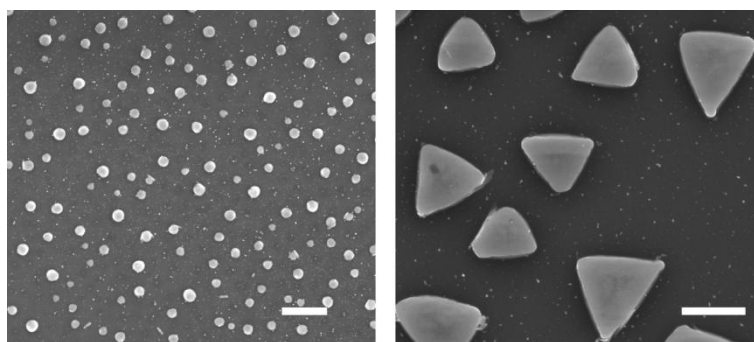


Figure S1. SEM images recorded on (left) the nanospheres and (right) the micro-triangles. Scale bar: 2 μm .

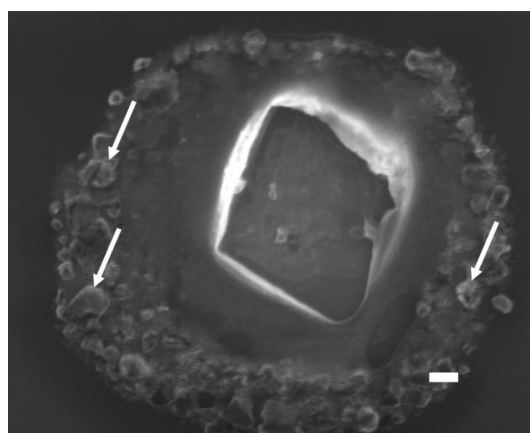


Figure S2. SEM image recorded on a nanocube after an excess in e-beam irradiation showing the formation of nanospheres (indicated in bright arrows) around the nanocube as a consequence to the surface diffusion of silver on the silicon substrate. Scale bar: 200 nm.

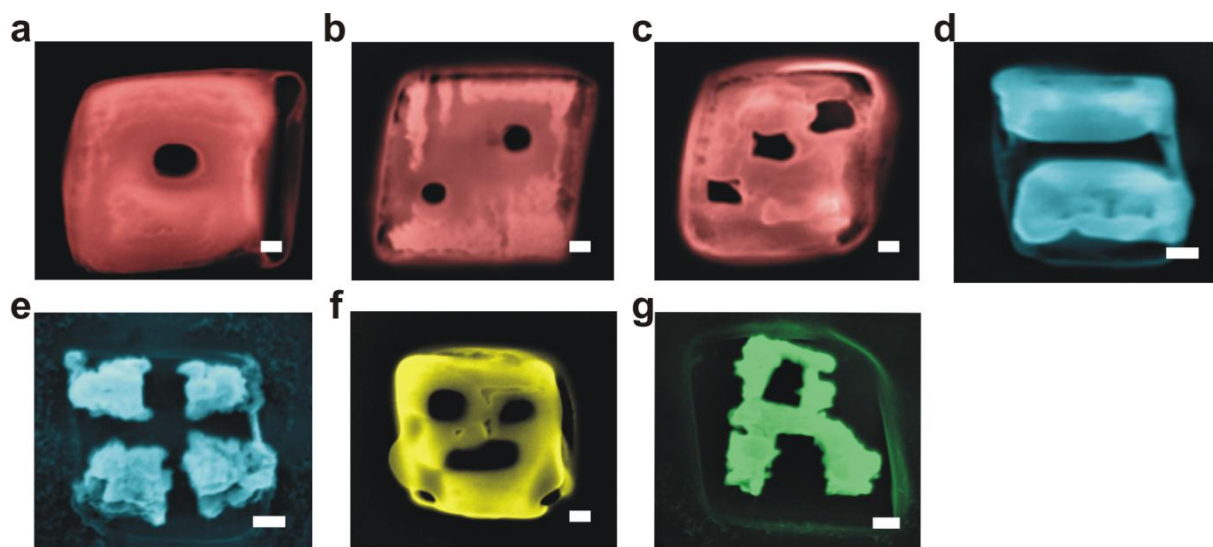


Figure S3. False colored SEM images of various structures that can be created by local etching of silver nanostructures using e-beam. a-d) three facets of a dice, d) silver nanocube cut in half, f) nanocube cut in four pieces, a) Smiley face and g) letter A. Scale bar: 100 nm.

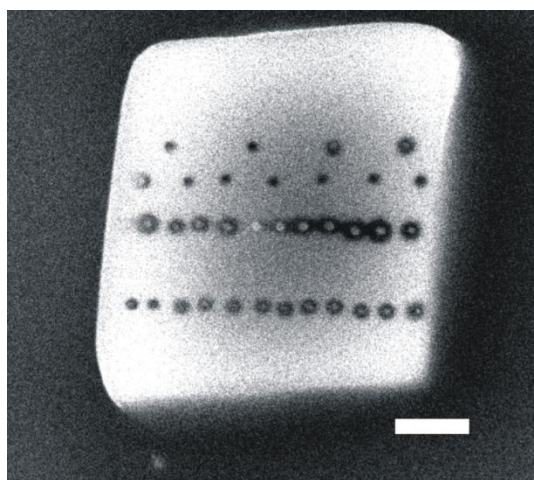


Figure S4. SEM image of a nanocube used to optimize the irradiation conditions. Scale bar: 200 nm.